

第五章 結論總結

1. PI/(Ta₂O₅-TaO_x)薄膜在含氧量越高的氣氛中退火越容易裂化，且薄膜的耐熱性有隨Ta₂O₅-TaO_x的添加量增加而下降的趨勢。
2. PI/(Ta₂O₅-TaO_x)薄膜的漏電流會隨著摻雜量的增加而增加。
3. 在退火溫度為 300 °C 下，PI/(Ta₂O₅-TaO_x)薄膜的漏電流在氧氣中最高，由於在氧氣的亞醯胺化程度最小，導致有游離電子的產生，因此漏電流密度較高。
4. PI/(Ta₂O₅-TaO_x)薄膜的介電常數與介電損失會隨摻雜量增加而增加。
5. 同一添加量下，PI/(Ta₂O₅-TaO_x)薄膜的介電常數會隨著退火氣氛含氧量的增加而遞增。
6. 在退火氣氛為氮氣下，PI/(Ta₂O₅-TaO_x)薄膜的介電常數與介電損失在 200°C~400°C 間的差異並不大。
7. PI/(Ta₂O₅-TaO_x)薄膜的介電損失受退火氣氛及退火溫度的影響不大。
8. 利用混合法製備聚亞醯胺二氧化鈦複合薄膜時，由於薄膜厚度要求在 5000Å，所以分散均勻的問題，仍是最大的關鍵因素。
9. X 光光電子光譜儀 (XPS) 可鑑定聚亞醯胺薄膜之亞醯胺化程度，並發現熱處理氣氛影響亞醯胺化程度。故可得知薄膜之漏電流與亞醯胺化程度有關。

10. 利用本實驗複合薄膜作成有機薄膜電晶體之介電層，由 $I_{DS}-V_G$ 關係圖中得知，隨著添加量的增加，載子移動率隨著介電常數增加而遞增，因此 I_{DS} 也隨之上升。



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